

REMARKS/ARGUMENTS

The above-identified patent application has been reviewed in light of the Examiner's Action dated March 30, 2005. Claims 7 and 8 have been amended. Claims 1-6 and 13-17 were previously withdrawn. Accordingly, Claims 7-12 are now pending in the present application

Regarding the indefiniteness rejection, Claim 7 has been amended to read "irradiated on a surface of an amorphous silicon film to form the polycrystalline silicon film." In view of this amendment, it is submitted that the rejection of Claim 7 as indefinite should be reconsidered and withdrawn.

Claims 7-12 were rejected as being unpatentable over Batra et al. (U.S. Patent No. 5,548,132 hereinafter "Batra") in view of Dohjo et al. (U.S. patent No. 4,975,760 hereinafter "Dohjo"). Applicant respectfully traverses this rejection since Batra does not disclose grain sizes of the whole of the drain and source that are set greater than a grain size of the channel based on the energy of laser light irradiated on a surface of an amorphous silicon film to form the polycrystalline silicon film, as recited in Claims 7 and 8. Rather, as shown in Fig. 5, Batra discloses that a grain size of the drain offset region 66 is set greater than a grain size of the remainder portion of the thin film layer 60, which includes the source and drain regions 70, 72 (see column 6, lines 5-20).

Dohjo discloses forming a gate electrode using an Mo-Ta alloy. However, Dohjo does not disclose grain sizes of the whole of the drain and source that are set greater than a grain size of the channel based on the energy of laser light irradiated on a surface of an amorphous silicon film to form the polycrystalline silicon film, as recited in claims 7 and 8. Accordingly, it is submitted that the present invention is not obvious over Batra in view of Dohjo.

Based upon the foregoing, Applicants believe that all pending claims are in condition for allowance and such disposition is respectfully requested. In the event that a telephone conversation would further prosecution and/or expedite allowance, the Examiner is invited to contact the undersigned.

Respectfully submitted,

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